



Timing characterization of 3D-trench silicon sensors



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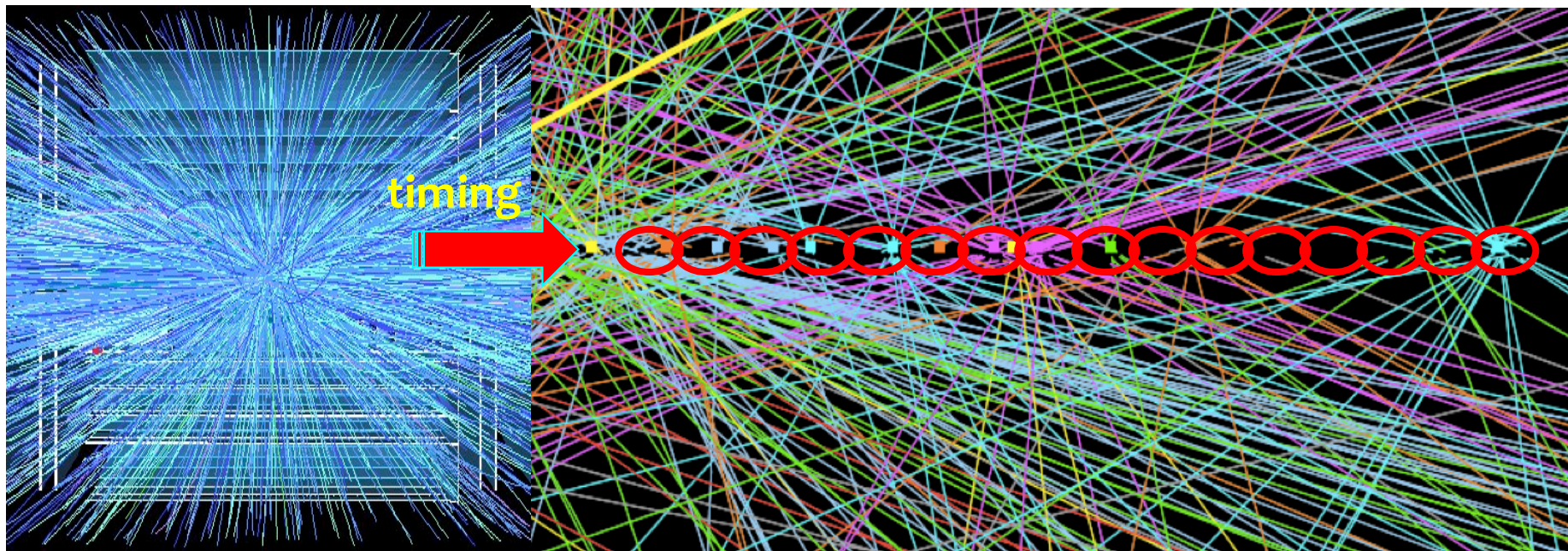


Scope of TIMESPOT R&D

TIME and SPace real time Operating Tracker

Scope:

Trend for future tracking at future colliders: Timing at the pixel level. Highly demanding characteristics



Crucial importance and strong interest in:

- ATLAS phase2 & CMS phase2 (Timing layers – LGAD based detectors)
- LHCb Upgrade 2 (Vertex detector: no technical solution yet, Ecal with timing)
- NA62 GTK upgrade
- FCC-hh, -ee ...

Structure, organization and objectives of

Project “specifications”

- Space resolution: $O(10 \mu\text{m})$
- Radiation hardness: $> 10^{16} \text{ 1 MeV } n_{\text{eq}}/\text{cm}^2$ (sensors) and $> 1 \text{ Grad}$ (electronics)
- Time resolution: $\leq 50 \text{ ps}$ per pixel
- Limited power per F/E channel (10's of μW)
- Real time track reconstruction algorithms and fast read-out (data throughput $> 1 \text{ TB/s}$)

4 years work
program (3+1)
2018–2021

Activities are organized in 6 work packages:

1. 3D silicon sensors: development and characterization
2. 3D diamond sensors: development and characterization
3. Design and test of pixel front-end
4. Design and implementation of real-time tracking algorithms
5. Design and implementation of high-speed readout boards
6. System integration and tests

Final Target:
Develop and realize a
demonstrator consisting
of a complete yet
simplified tracking
system, integrating
 $O(1000)$ read-out pixels

10 Italian Institutes: Bologna, Cagliari, Genova, Ferrara, Firenze, Milano, Padova, Perugia,
Torino, TIFPA. ≈ 60 heads, ~ 25 FTE. LHCb, ATLAS, CMS + others

3D silicon sensors: key performance points

Established (well known) properties

- Short inter-electrode drift distance (tens of μm): extremely fast signals
- Strong mitigation of Landau fluctuation by geometry
- Un-matched radiation hardness ($> 10^{16} \text{ 1 MeV n}_{\text{eq}}/\text{cm}^2$)
- 3D column geometry is a production ready technology (ATLAS IBL, ATLAS-ph2)

3D and timing (some history)

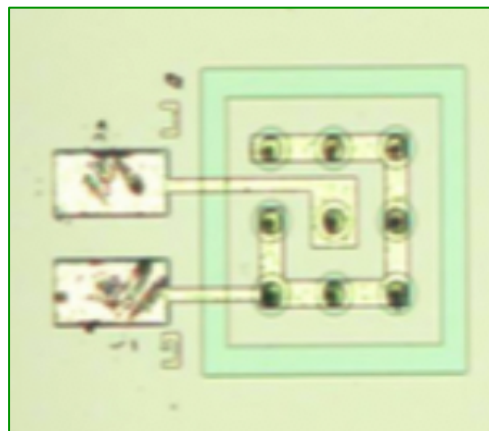
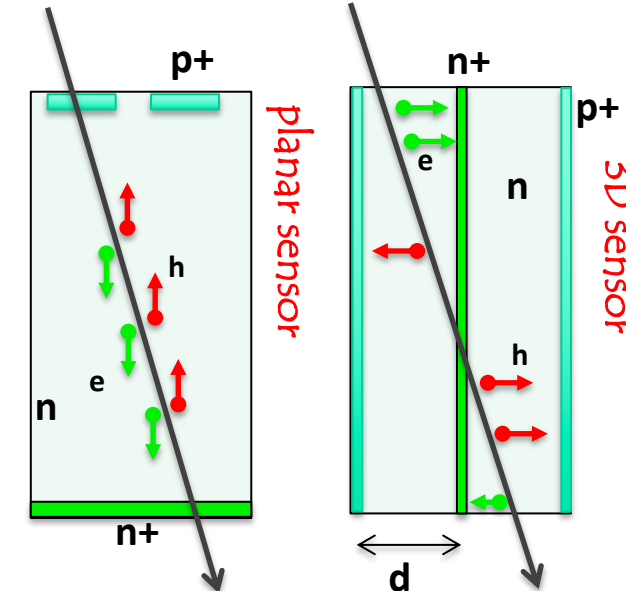
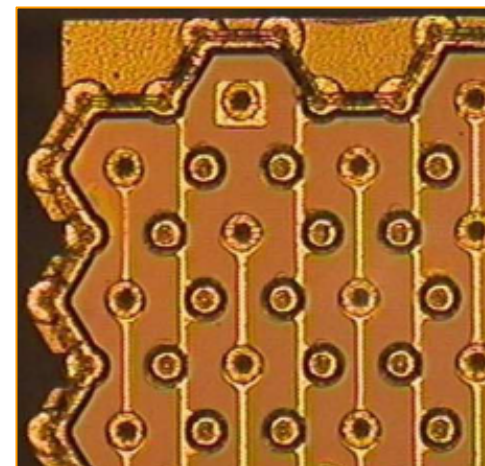
S. Parker et al. IEEE TNS 58(2) (2011) 404

Column hexagonal geometry $l=50 \mu\text{m}$. 20 V bias

Tested under ^{90}Sr β source. Room temperature

σ_t ranges from 177 to 31 ps (according to signal amplitude)

Limited by RO electronics noise



G. Kramberger et al., NIMA 934 (2019) 26-32

Square geometry $l=50 \mu\text{m}$. Depth = $300 \mu\text{m}$. 50 V bias

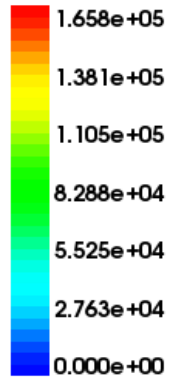
Tested under ^{90}Sr β source. Room temperature.

$\sigma_t = 75 \text{ ps}$. Dominated by hit position inside cell (time walk)

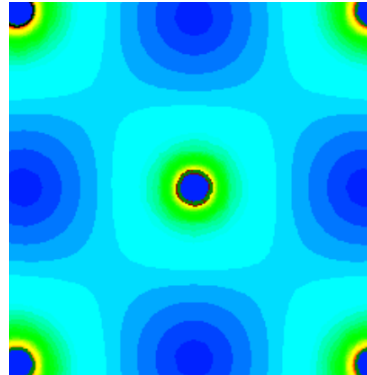
Preliminary tests (TREDI 2020 Workshop) with ^{106}Ru source give resolutions $\sigma_t \approx 40 \text{ ps}$ (to be better verified)

3D-trench geometry and characteristics

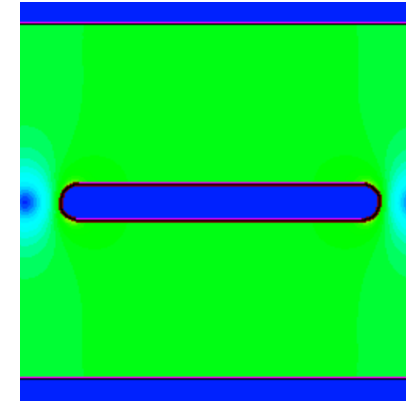
Abs(ElectricField-V) (V*cm⁻¹)



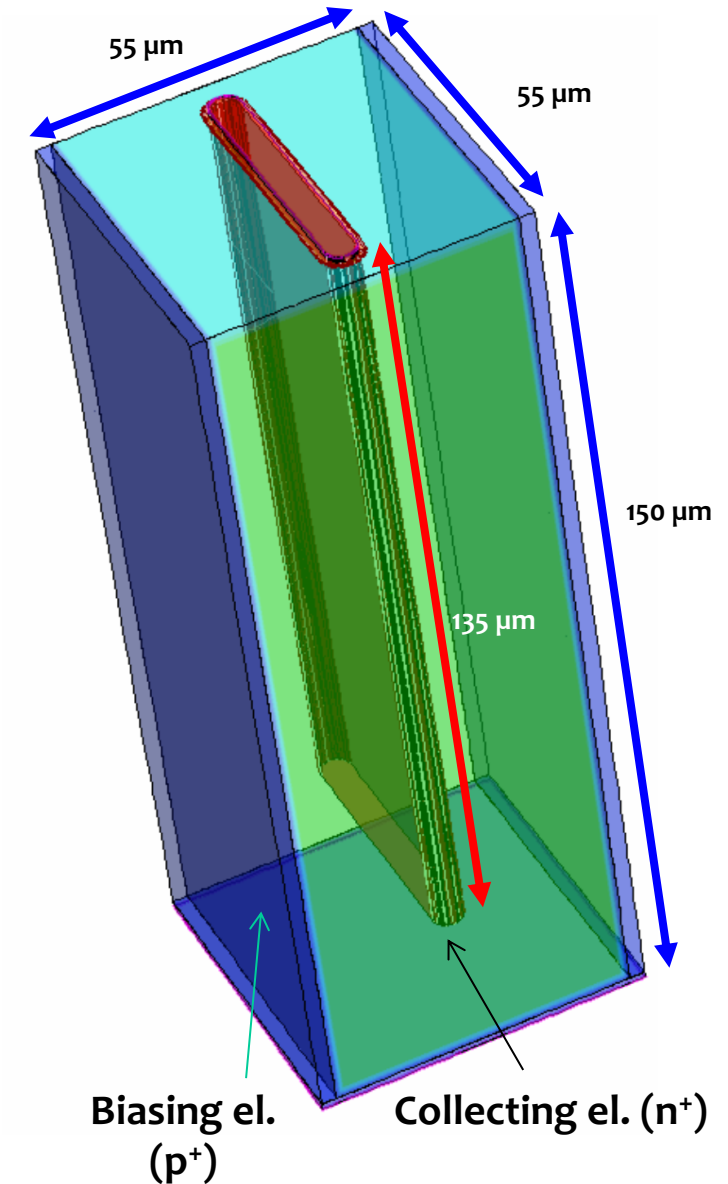
Electric field
map @ 100 V
bias



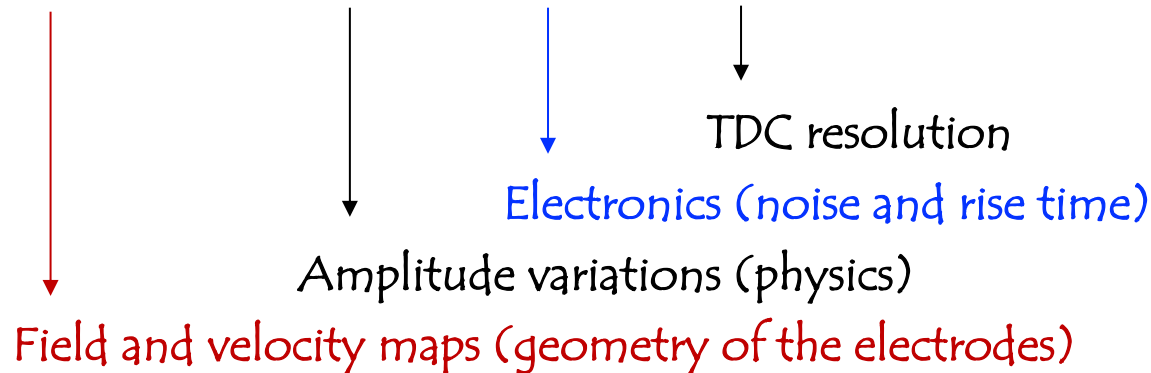
Column square geometry
(e.g. ATLAS ITk phase2)



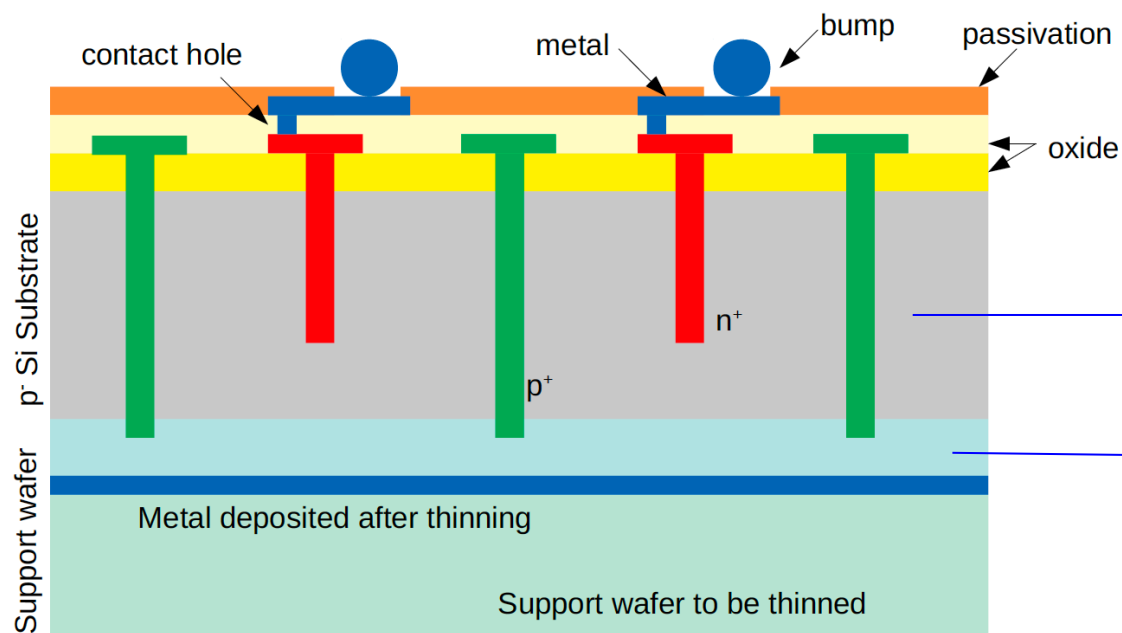
Trench geometry
(TIMESPOT)



$$\sigma_t^2 = \sigma_{disunif}^2 + \sigma_{TW}^2 + \sigma_{elJ}^2 + \sigma_{TDC}^2$$



3D-trench geometry and characteristics (2)

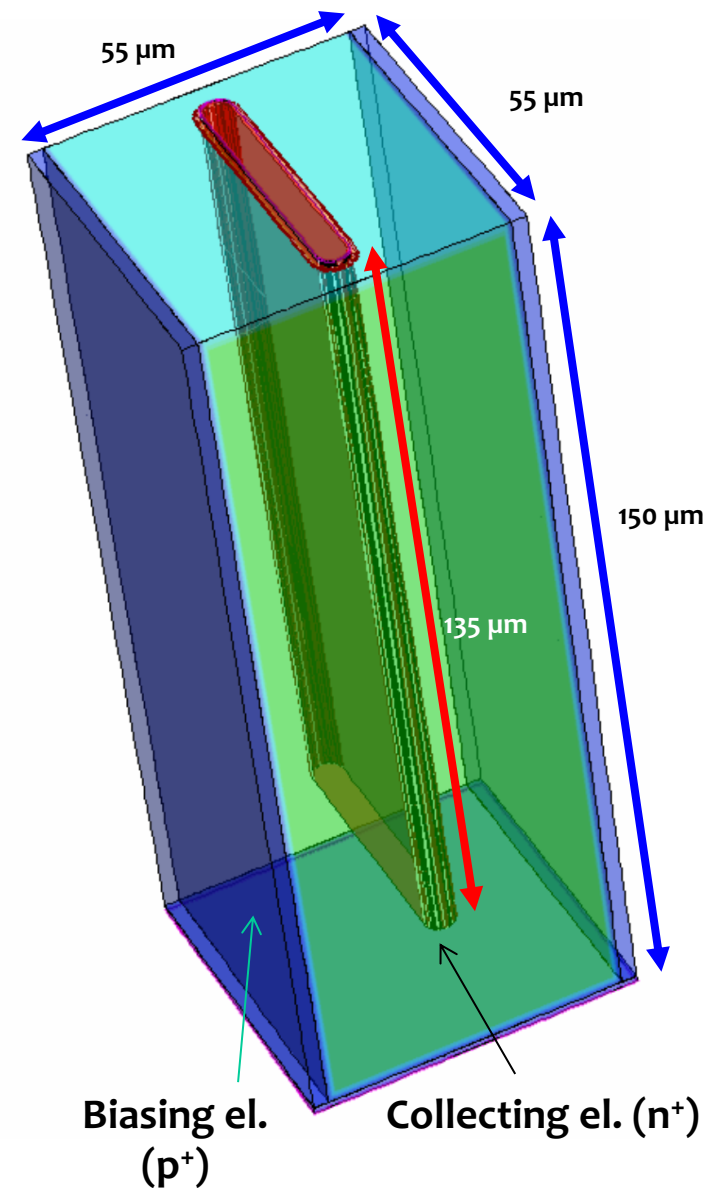


HR Si ($\sim 5\text{k}\Omega\text{ cm}$)
(sensitive volume)

LR Si ($<\Omega\text{ cm}$)

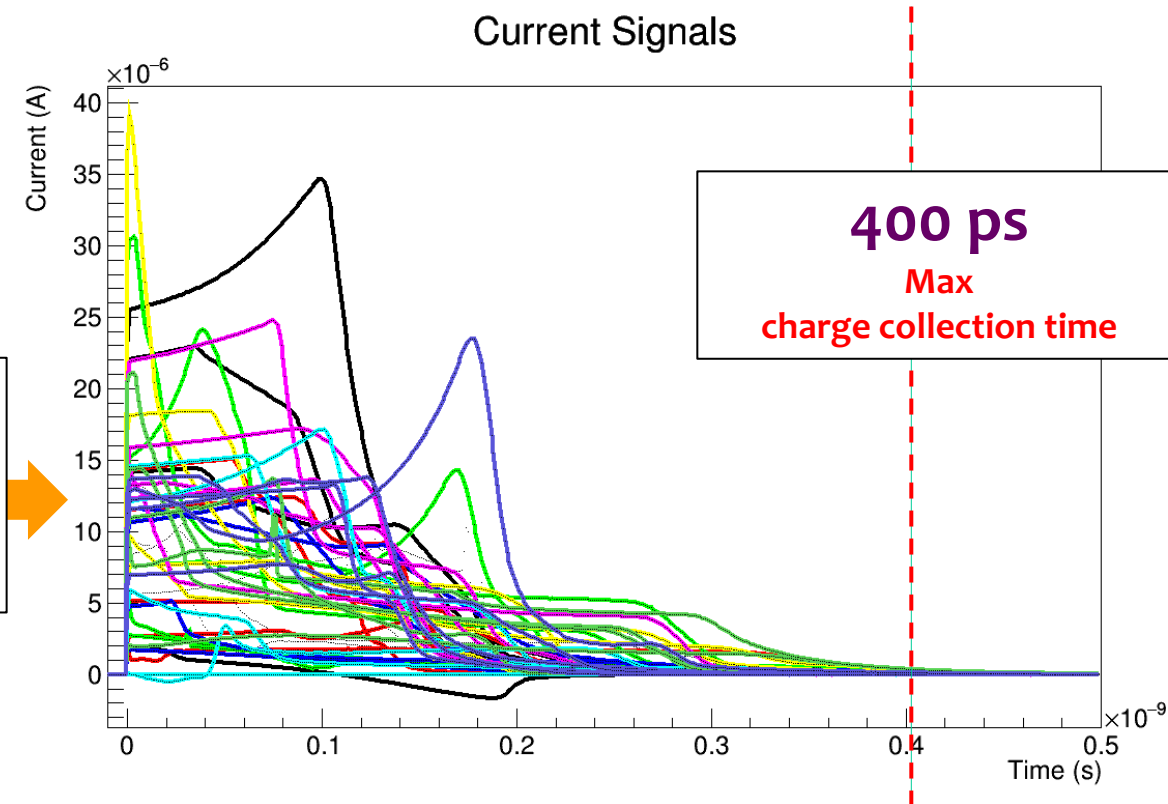
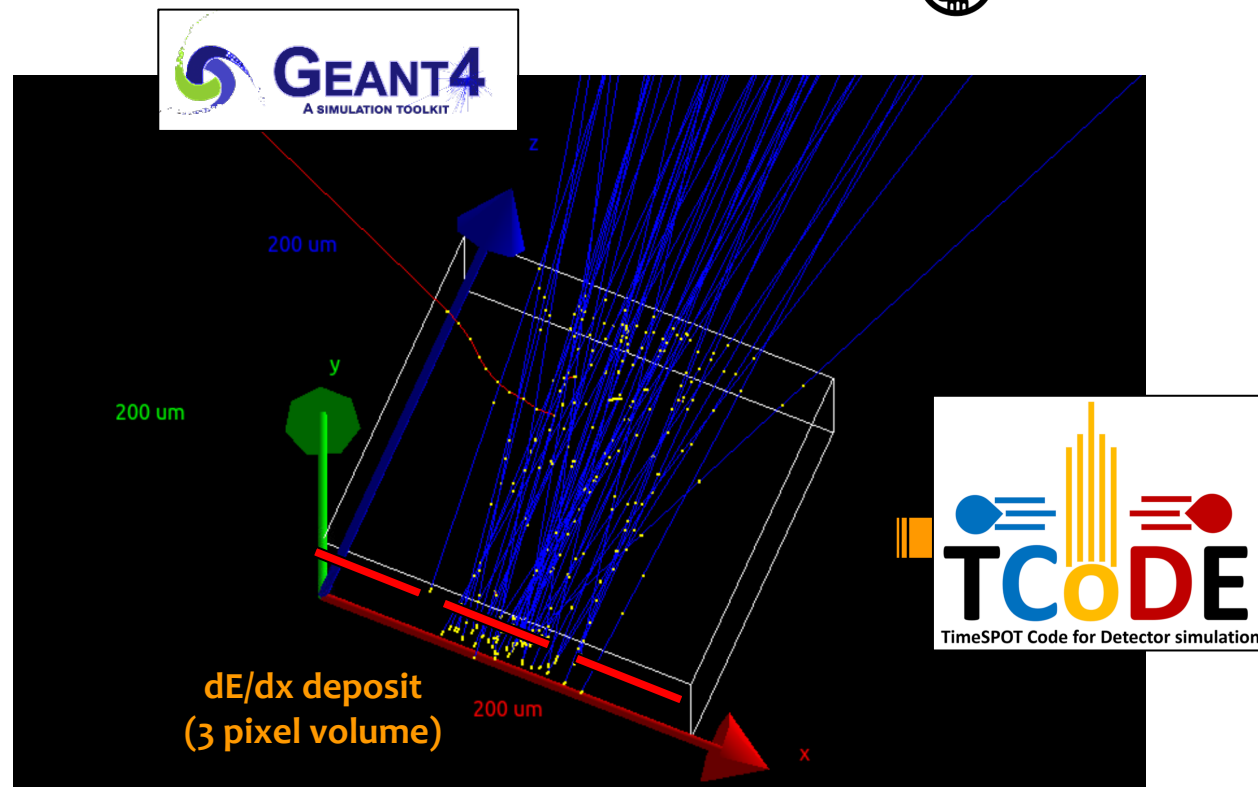
**Single-Side
production method**

- Total charge deposit for MIP $\approx 2\text{ fC}$
- Full depletion @ few Volts, Velocity saturation @ $> 30\text{ V}$
- Pixel capacitance (from simulation) $\sim 110\text{ fF}$
- $55 \times 55\text{ }\mu\text{m}^2$: TIMEPIX family-compatible pitch



Signals: full-3D model. “Statistics”

<https://github.com/MultithreadCorner/Tcode>



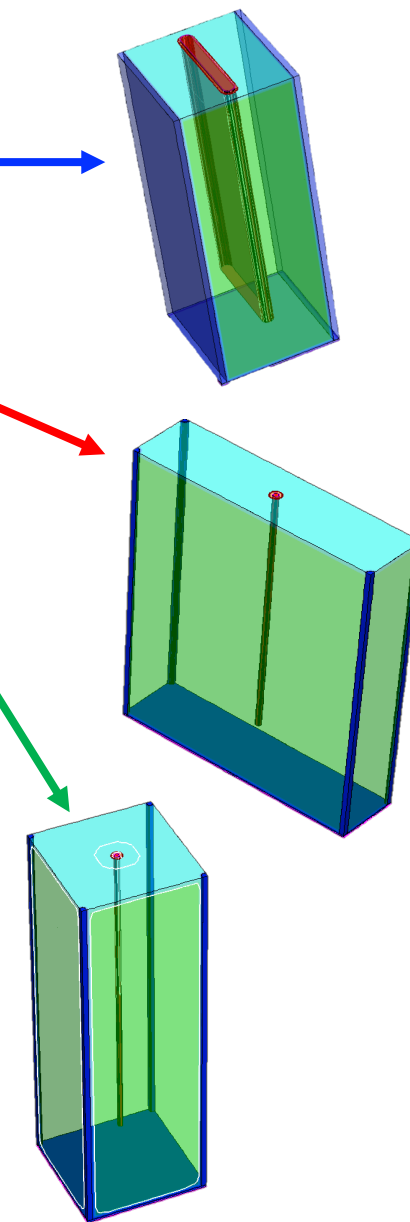
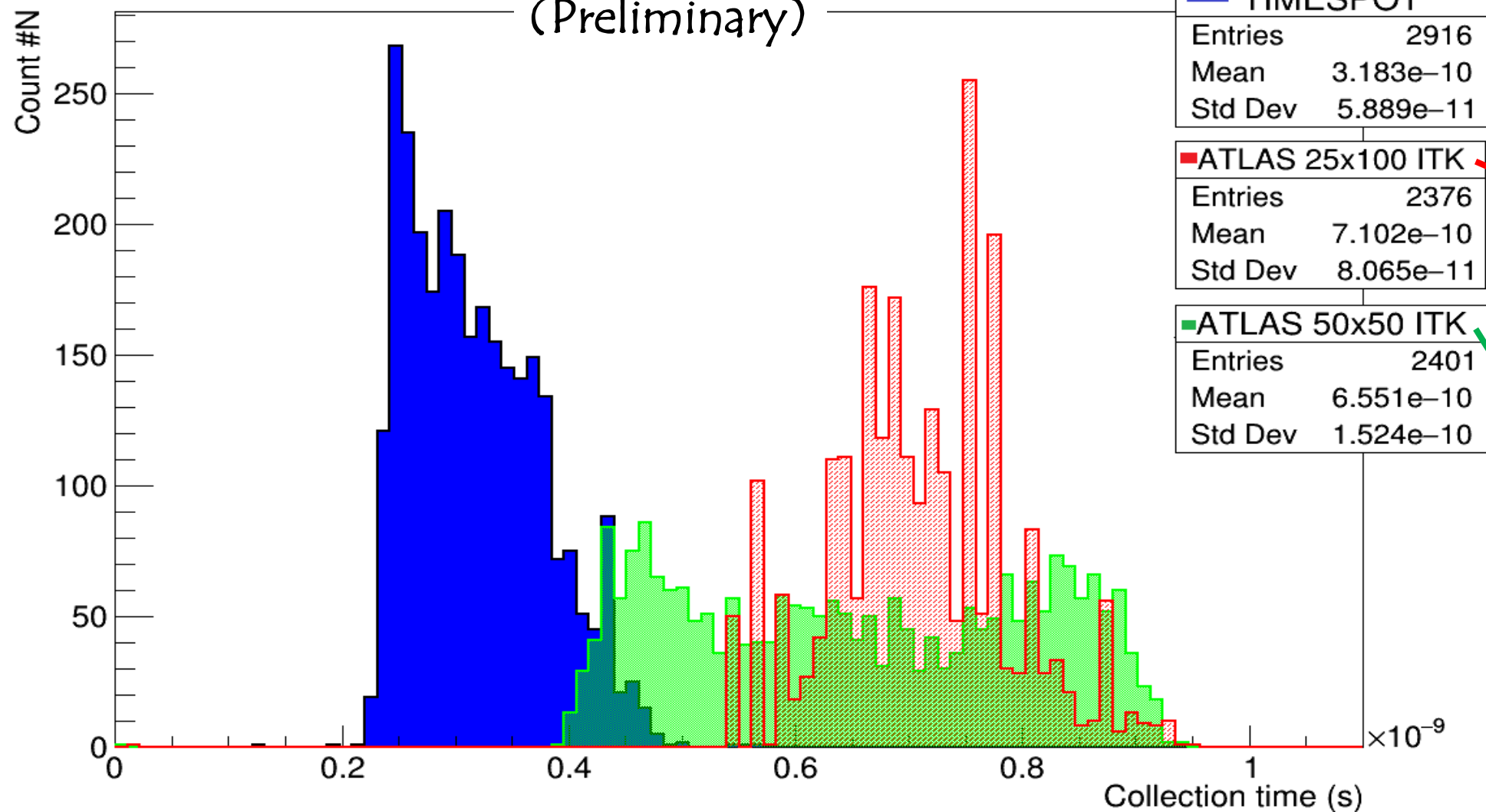
Geant4 generated dE/dx deposit

Electric, Weighting and Velocity fields map from **TCAD Sentaurus**

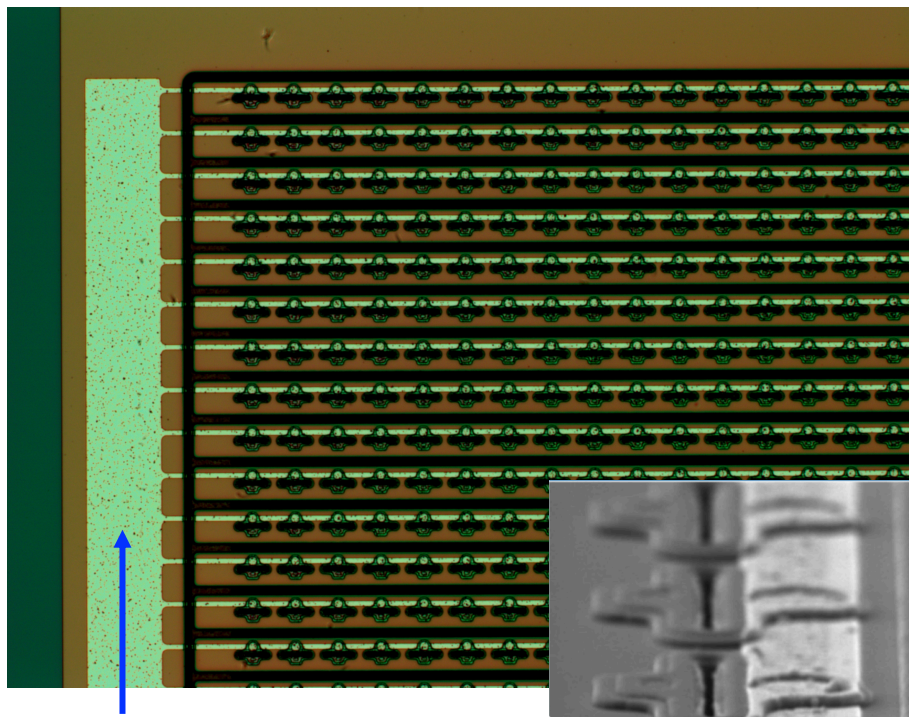
Carrier dynamics from **TCODE** custom multithread code

Signals: full-3D model. 3D geometry comparison

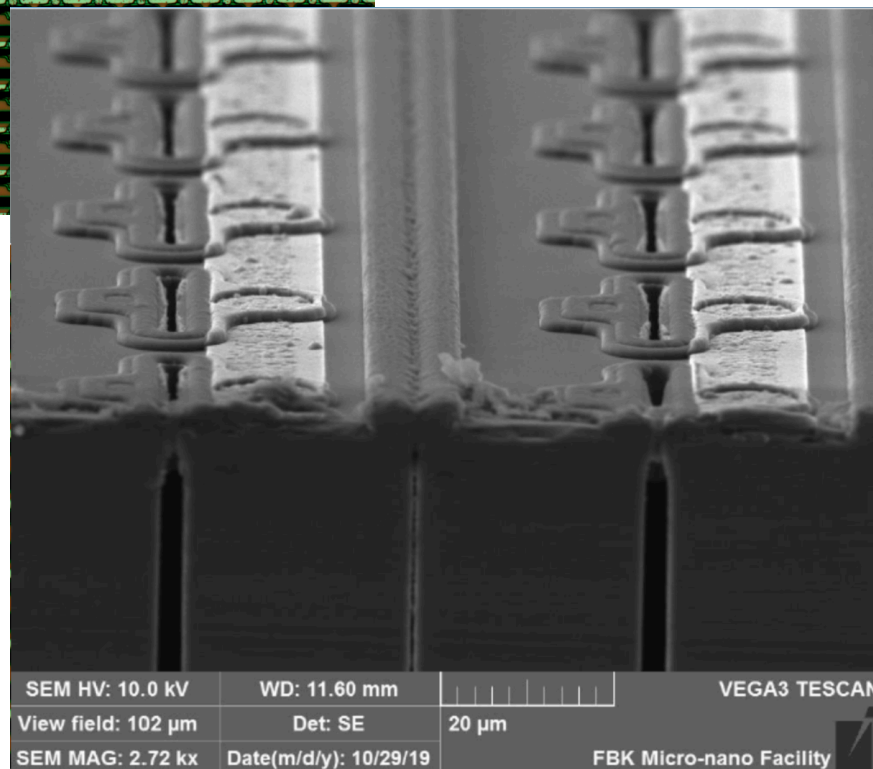
Charge Collection time after 3σ of collected charge
(Preliminary)



1st 3D-trench batch: delivered June 2019



Temporary metal
(removed after static
electric measurements)
Portion of a 256x256
pixel matrix

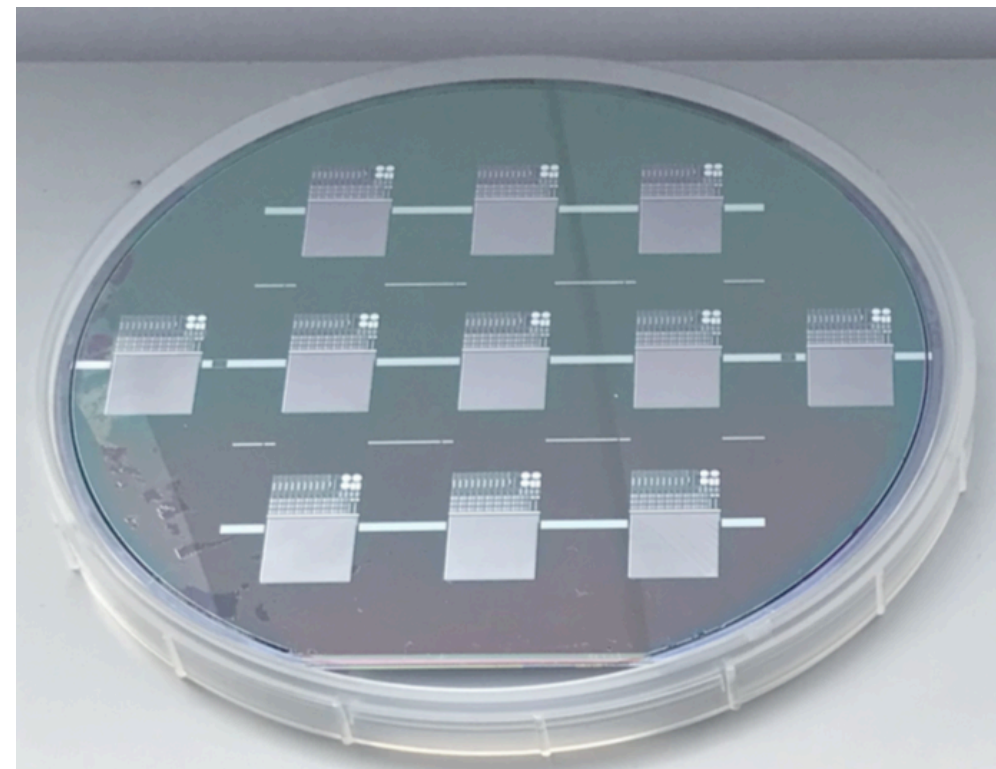


Photolithography with stepper machine. Characteristics:

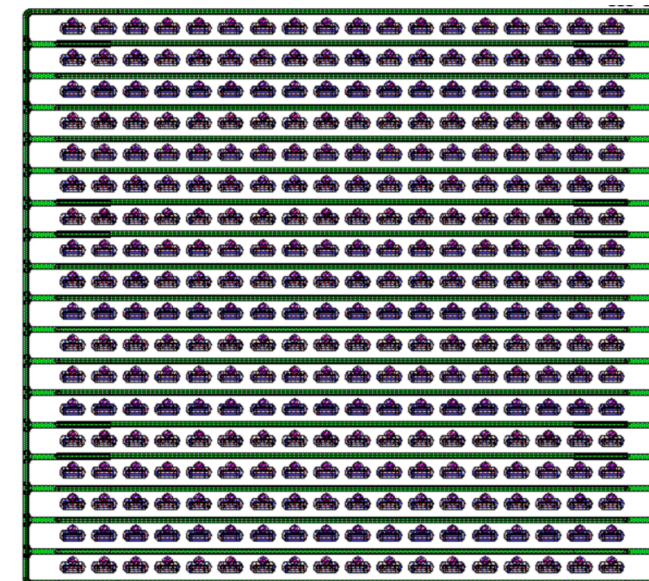
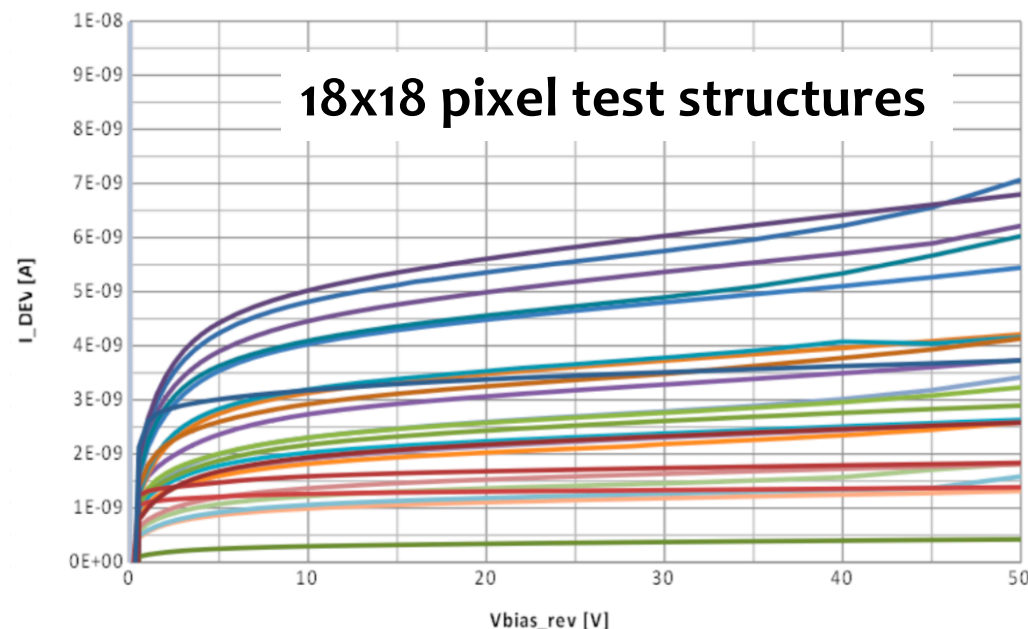
- Minimum feature size 350 nm
- Alignment accuracy 80 nm
- Max exposure area ~2x2 cm²
- Full size reticle for two blocks:
Timepix sensor and test structures



10x 6 inches wafer



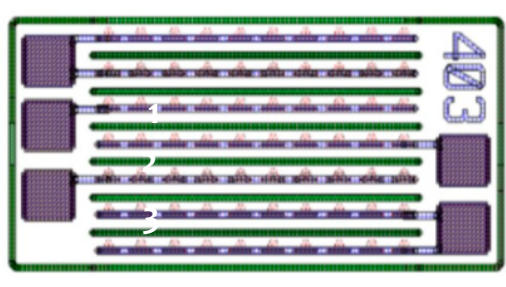
1st 3D-trench batch: Electrical («static») characterization



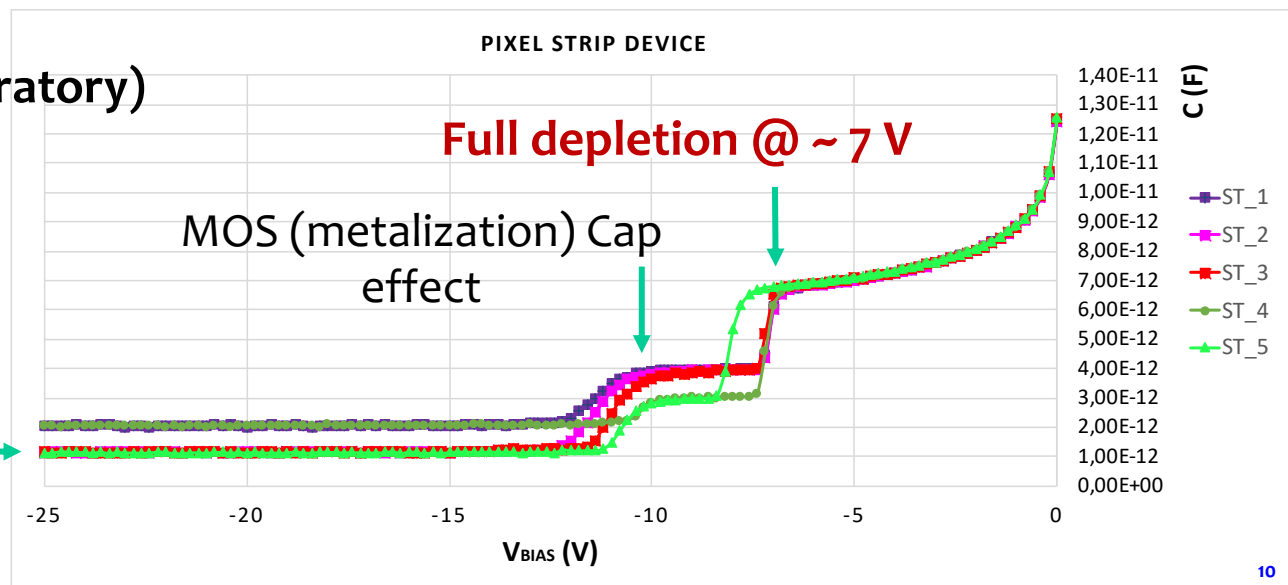
Measurements on wafer (FBK)

~10 pA/pixel on good devices

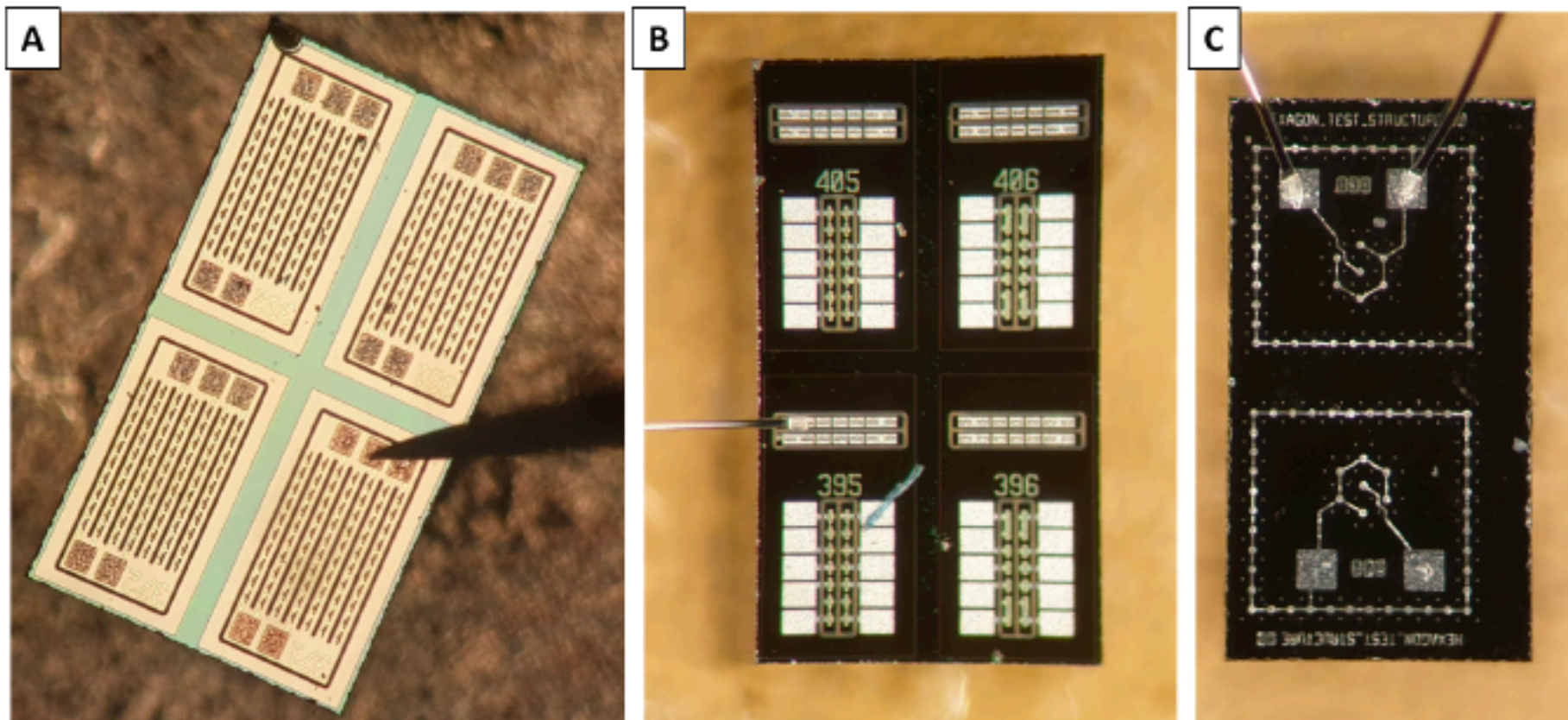
Measurements after dicing (Torino and Trento laboratory)



Measured capacitance ~100 fF/pixel
(in agreement with simulation)



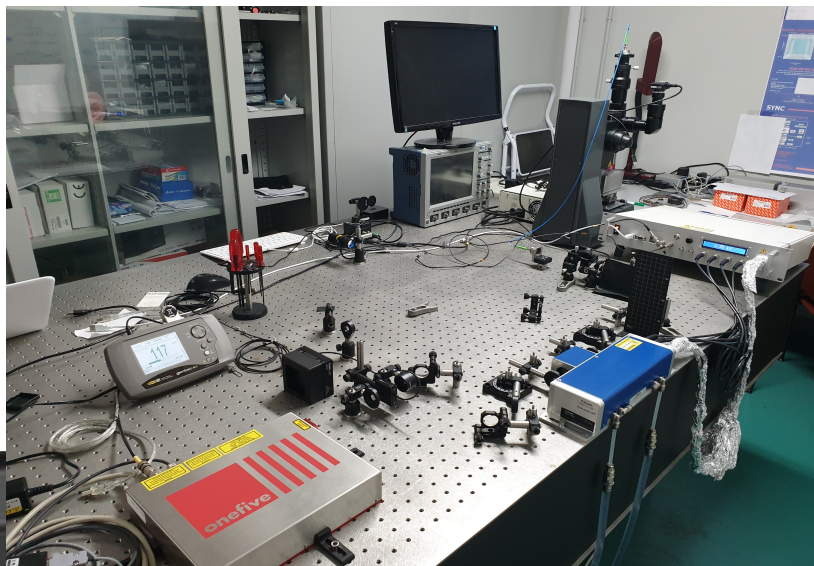
3D structures under «dynamic» tests In lab & under-beam measurements



(A) Pixel-strip (10 pixels connected on the same read-out pad); **(B)** Single and double pixel; **(C)** Hexagonal (column) pixel device, based on FBK 3D Double Side Technology (not from TIMESPOT batch).
Devices are connected to electronics by wire bonding (Al, 25 μm diameter, ~ 5 mm length)

Laser on test structures

Measurements on 1st batch in Cagliari lab



Test setup:

1030 nm pulsed LASER
200 fs native jitter

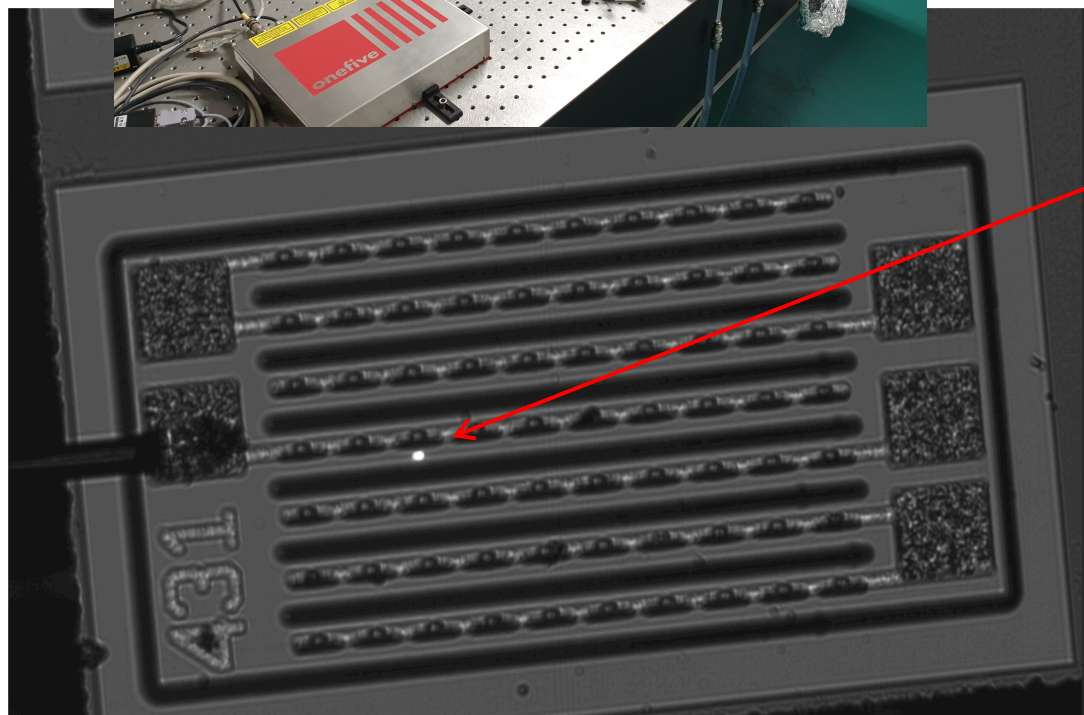
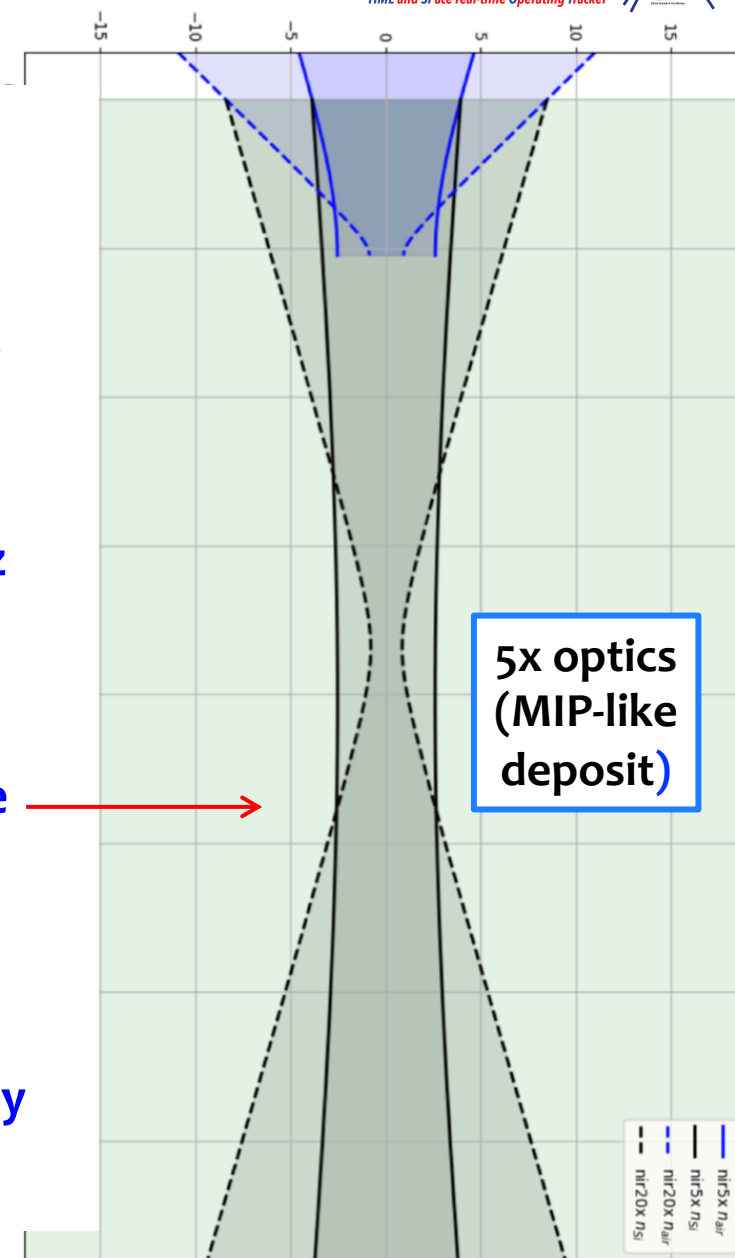
1 ps on scope (“setup” jitter)

Repetition rate from single pulse to 40 MHz

Cylindrical spot 5 μm diameter

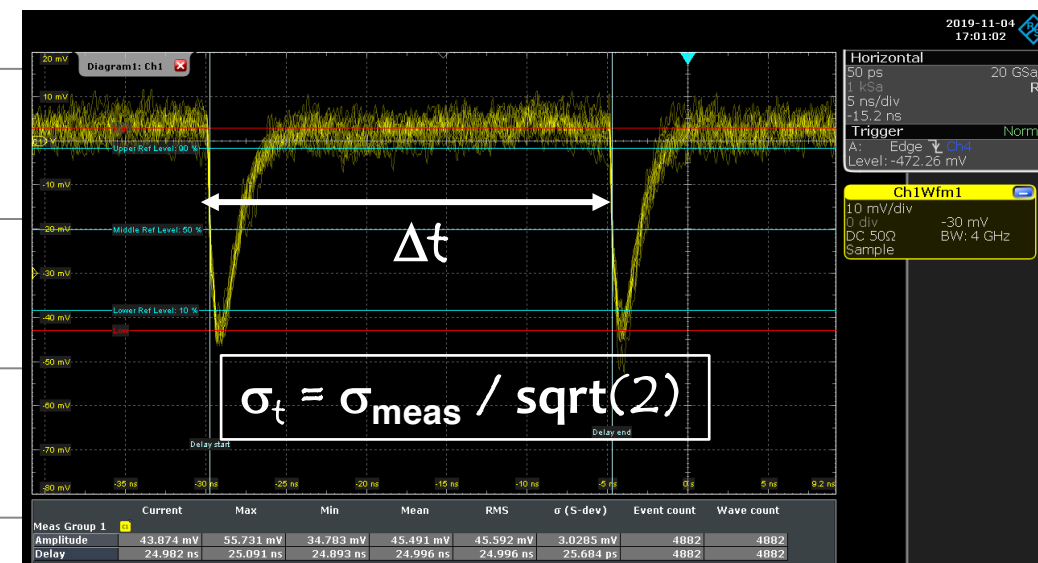
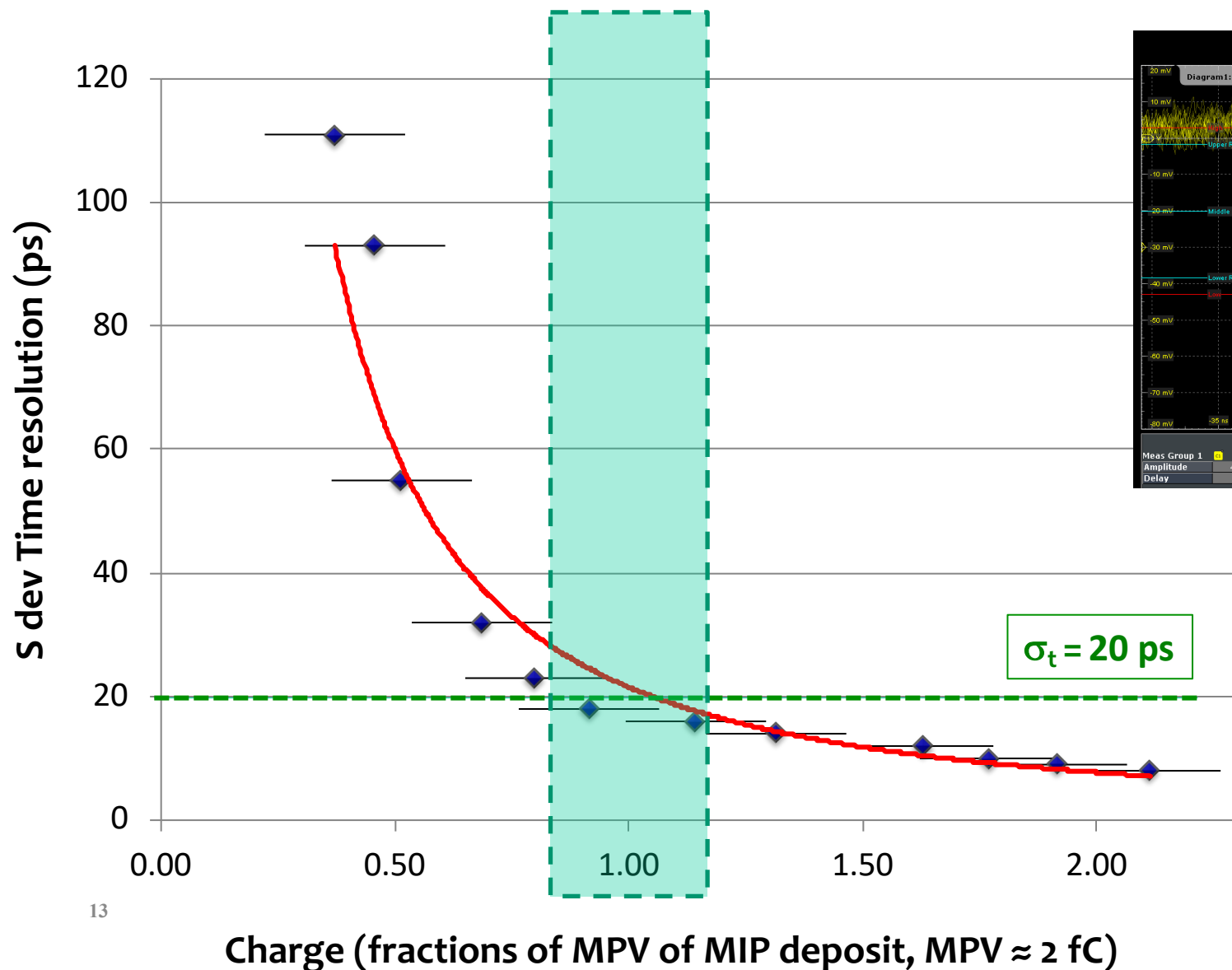
MIP-like deposit shape

MIP (~ 2 fC) deposit amount estimated by means of Charge amplifier, adjustable by optical filtering



Pixel strip device: 10 pixels read-out together

Time response vs Charge



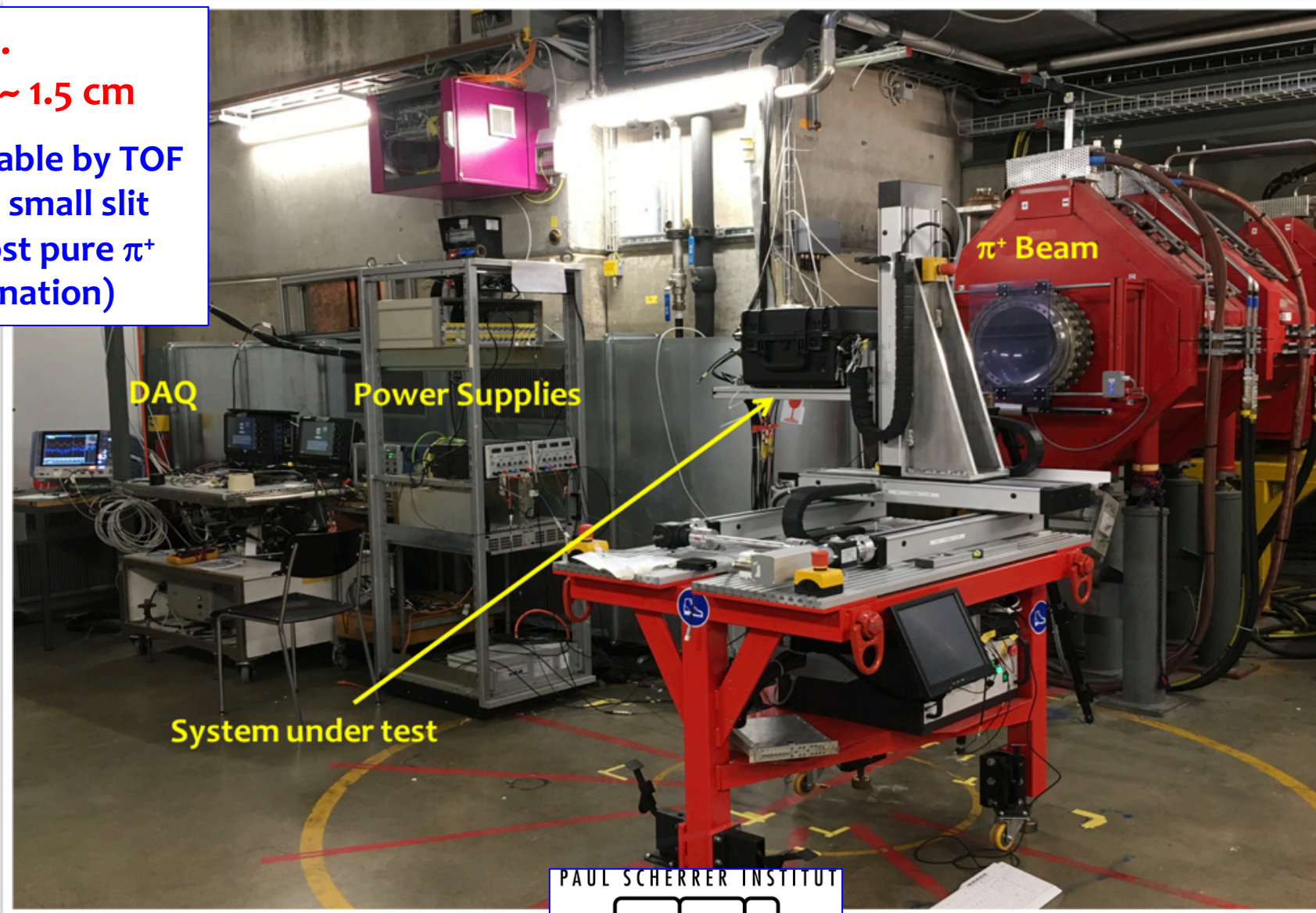
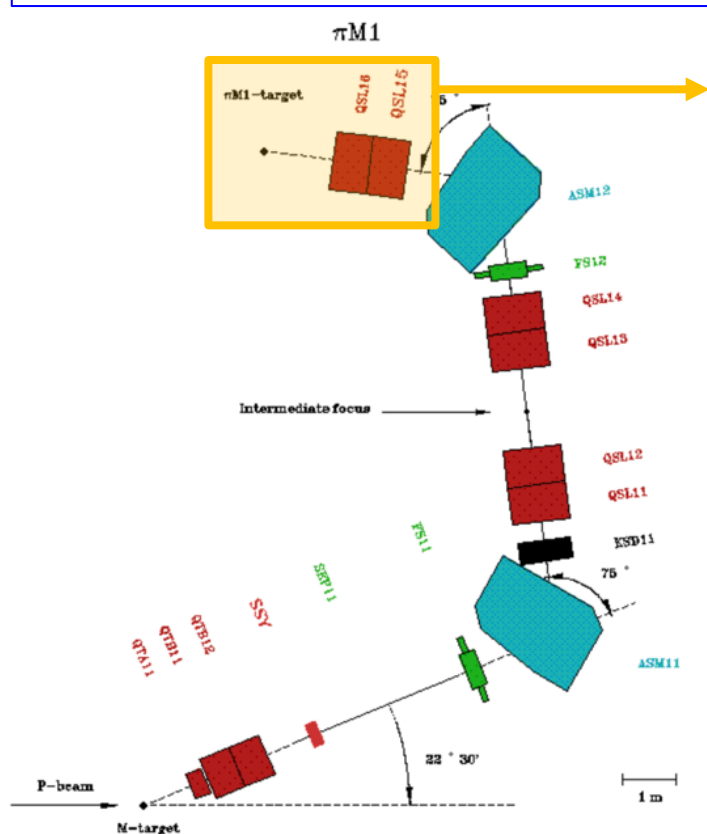
- Pixel Strip @ $V_{\text{bias}} = -60 \text{ V}$ @ room temperature
- Discrete component Front-end from Kansas University design (not optimized)
- Numerical CFD (on scope)
- 10 pixel strip + wire bond connection ($C_{\text{tot}} \approx 1.5 \text{ pF}$)
- Charge deposit estimate by separate calibrated CSA readout

Tests beam @ PSI accelerator ($\pi M1$)

Beam $E = 270$ MeV/c.

Beam radius on the spot $\sigma \sim 1.5$ cm

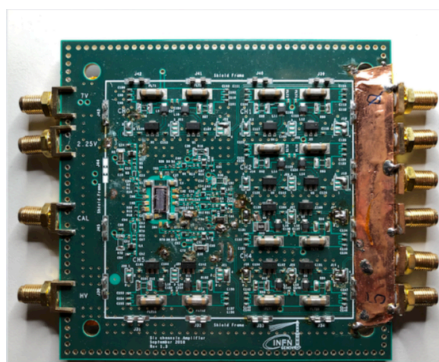
Original beam: p, e^+, μ^+, π^+ Selectable by TOF
Using a plexiglas degrader and small slit apertures we obtained an almost pure π^+ beam (negligible e^+ contamination)



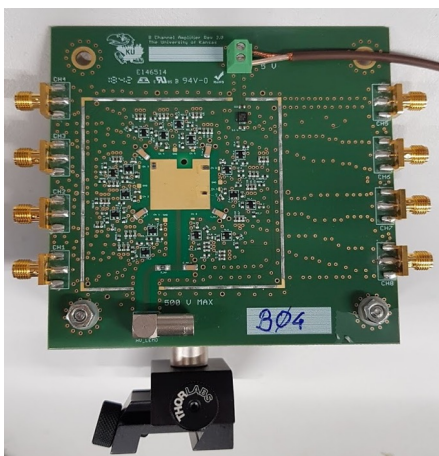
Tests beam @ PSI π M1

System inside the black box

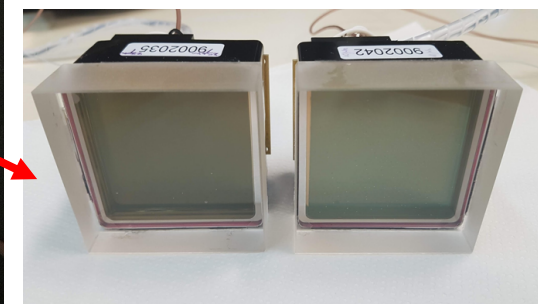
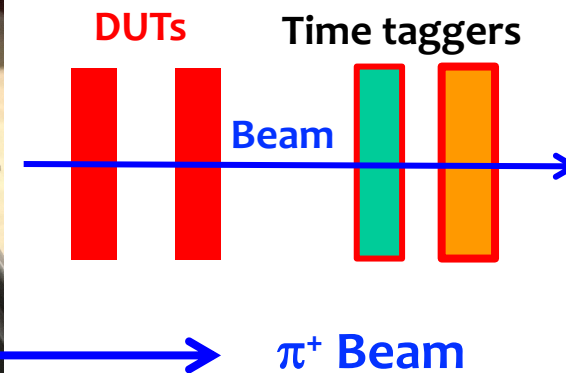
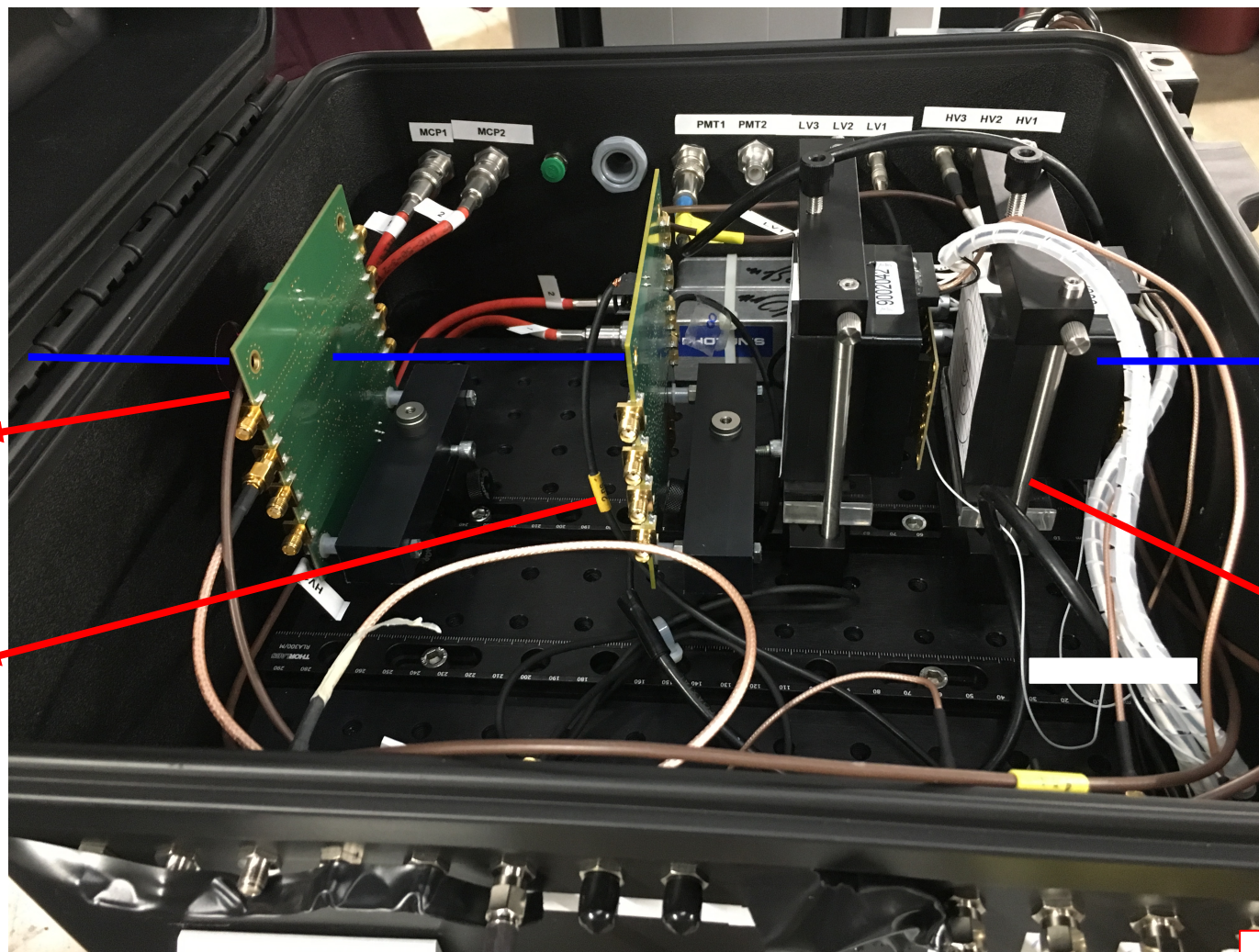
DUT front end:
broadband amplifier board with discrete components



INFN-Ge Front End



KU Front End



Time Taggers:
Quarz Cherenkov
radiator + MCP

$$\sigma_t \approx 15 \text{ ps (each tagger)}$$

Tests beam @ PSI $\pi M1$

Waveforms acquired

DUT signal (trigger)
Exposed Area of DUTs

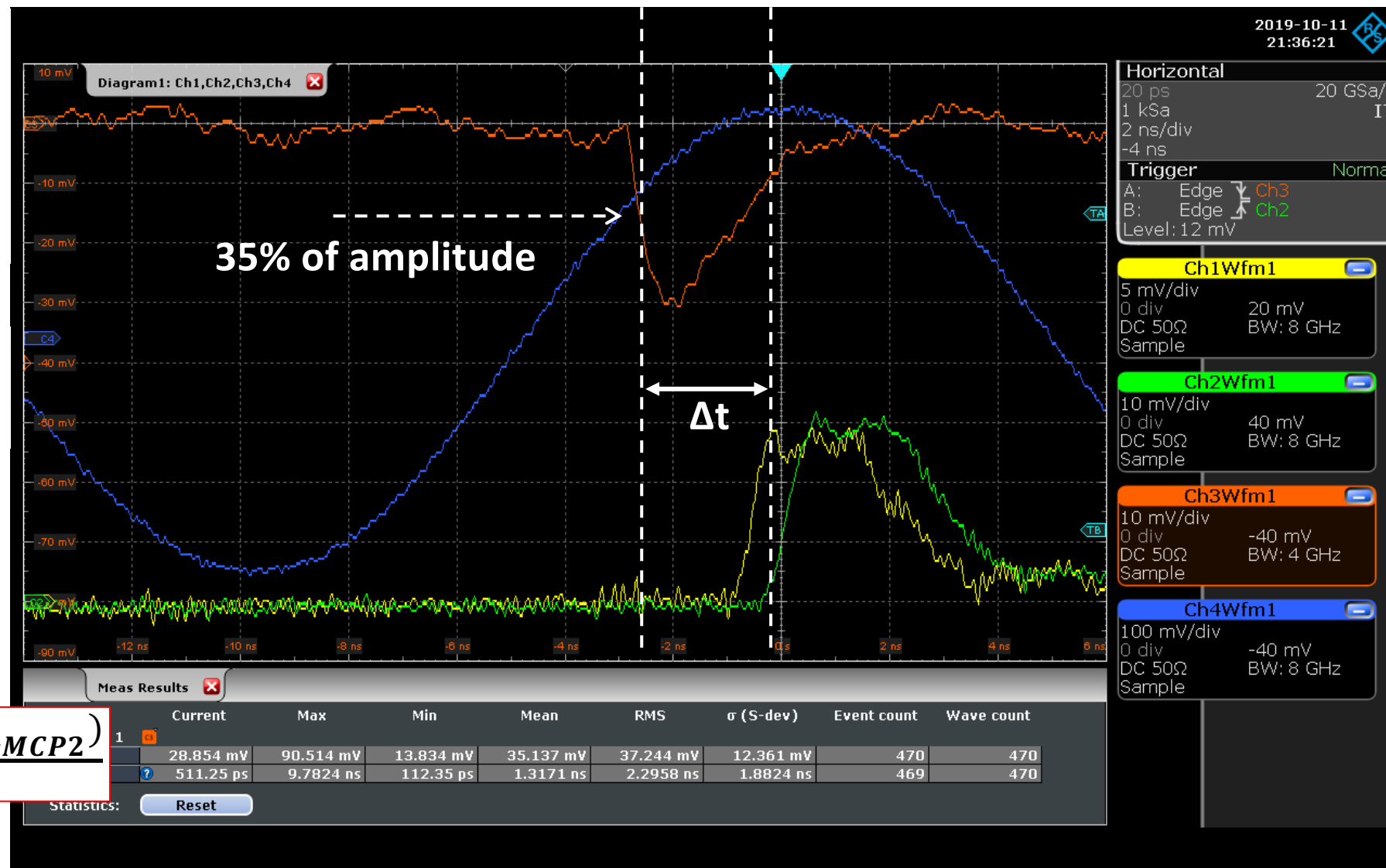
$\ll 1 \text{ mm}^2$

Each DUT has a different DAQ chain (8 GHz BW scope)

Beam RF signal
(50 MHz)

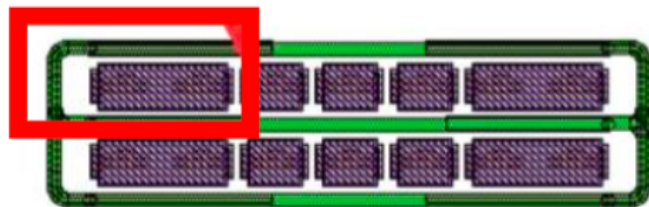
2 MCP signals
(time references)
Exposed area $\approx 5 \times 5 \text{ cm}^2$

$$\Delta t = t_{hsgn} - \frac{(t_{thMCP1} + t_{thMCP2})}{2}$$

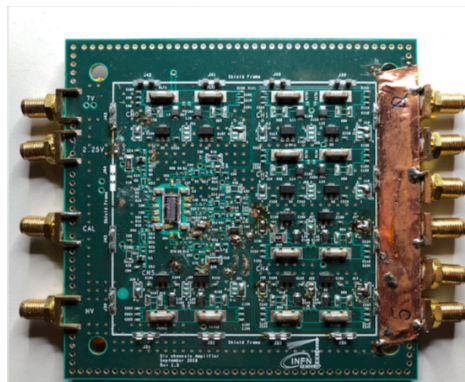


Test beam results

Measurements depends strongly on the specific F/E electronics used.
In the following, results obtained with DUT2 (INFN-GE F/E are illustrated)



DUT: Double pixel

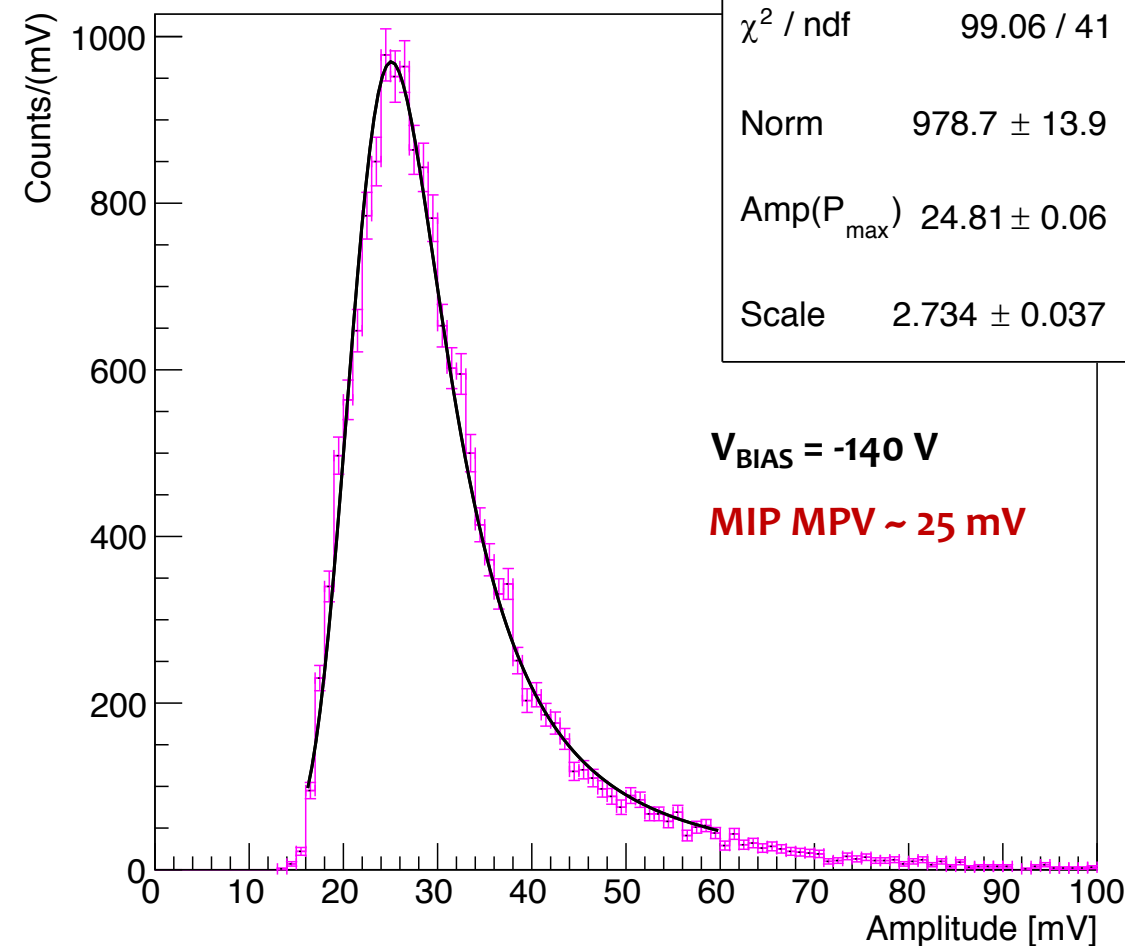


INFN-Ge Front End Board
(1 amplification stage, $G \sim 30$
2 GHz bandwidth)

+ **external broadband amplifier**
($G=10$, 2 GHz bandwidth)

V_{BIAS} (V)	N of events
-20	20k
-50	20k
-80	3k
-110	20k
-140	20k

Measurements performed
at different V_{BIAS}

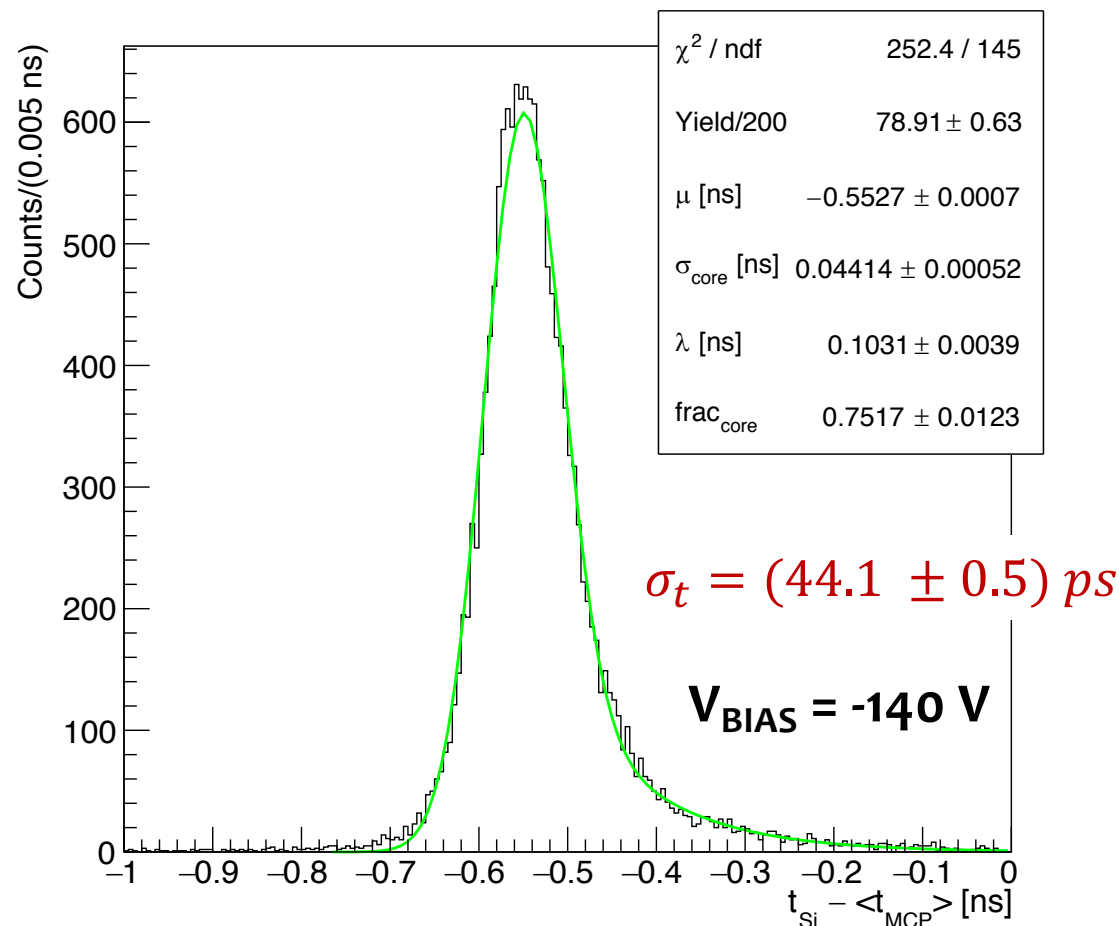


FIT: Gaussian (noise) + Landau (signal) + error step function (trigger)

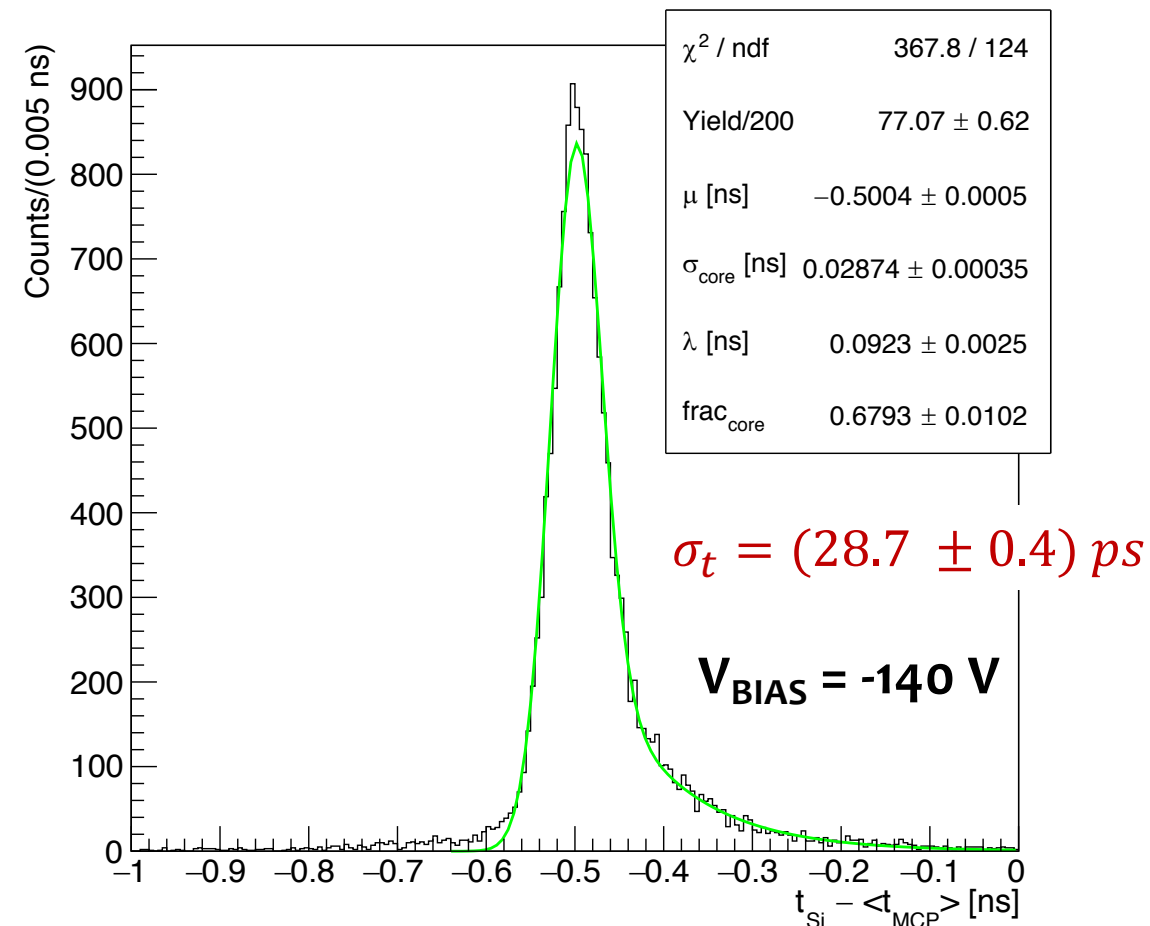
The Max/FWHM ratio is compatible with a Landau distribution of a 150 μm thick silicon

Test beam results: Time resolution

- 👉 ToA: numerical **leading edge** discriminator with a fixed threshold $Th=5mV$ (no TOT correction)

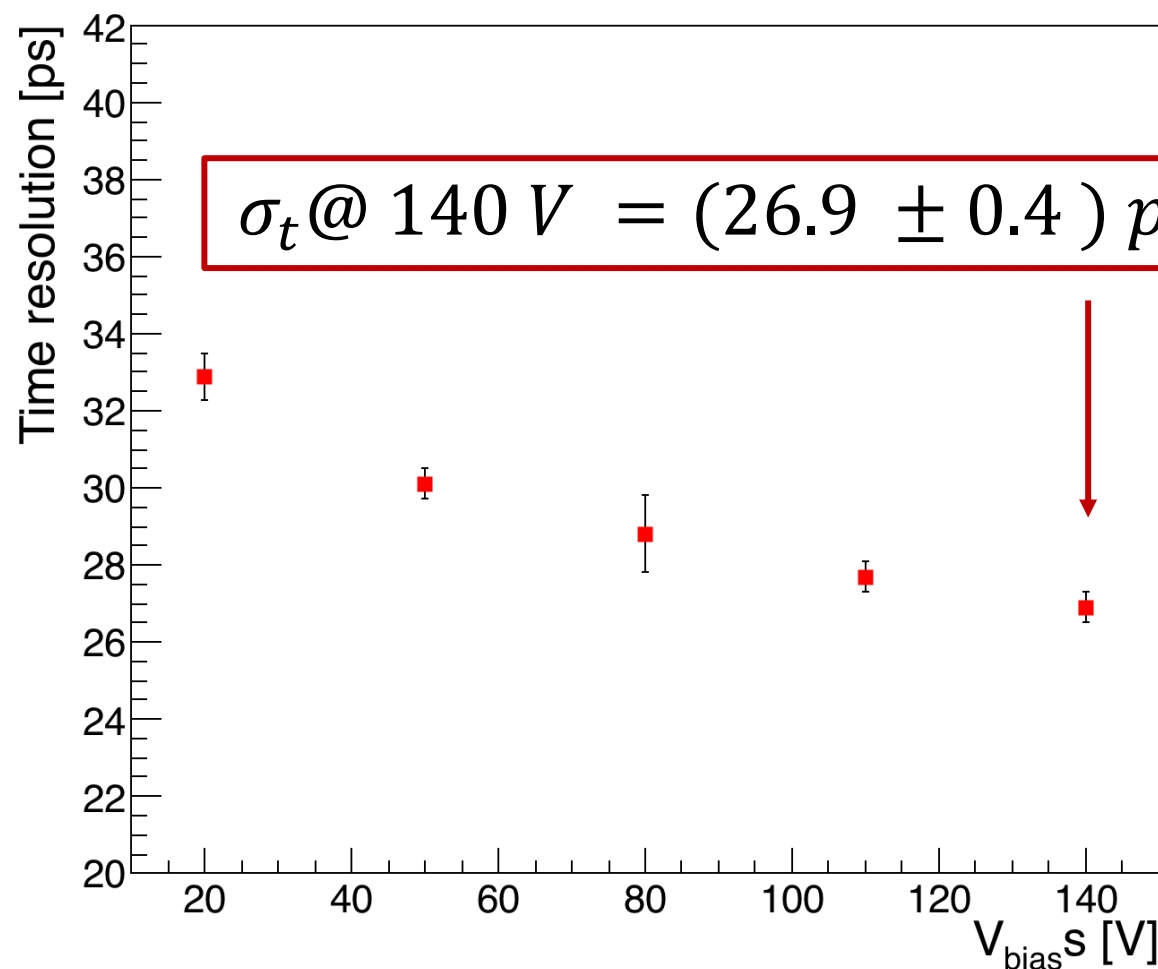


- 👉 Numerical filters to reduce high frequency noise applied
- 👉 ToA: Numerical **CFD** with a 35% threshold

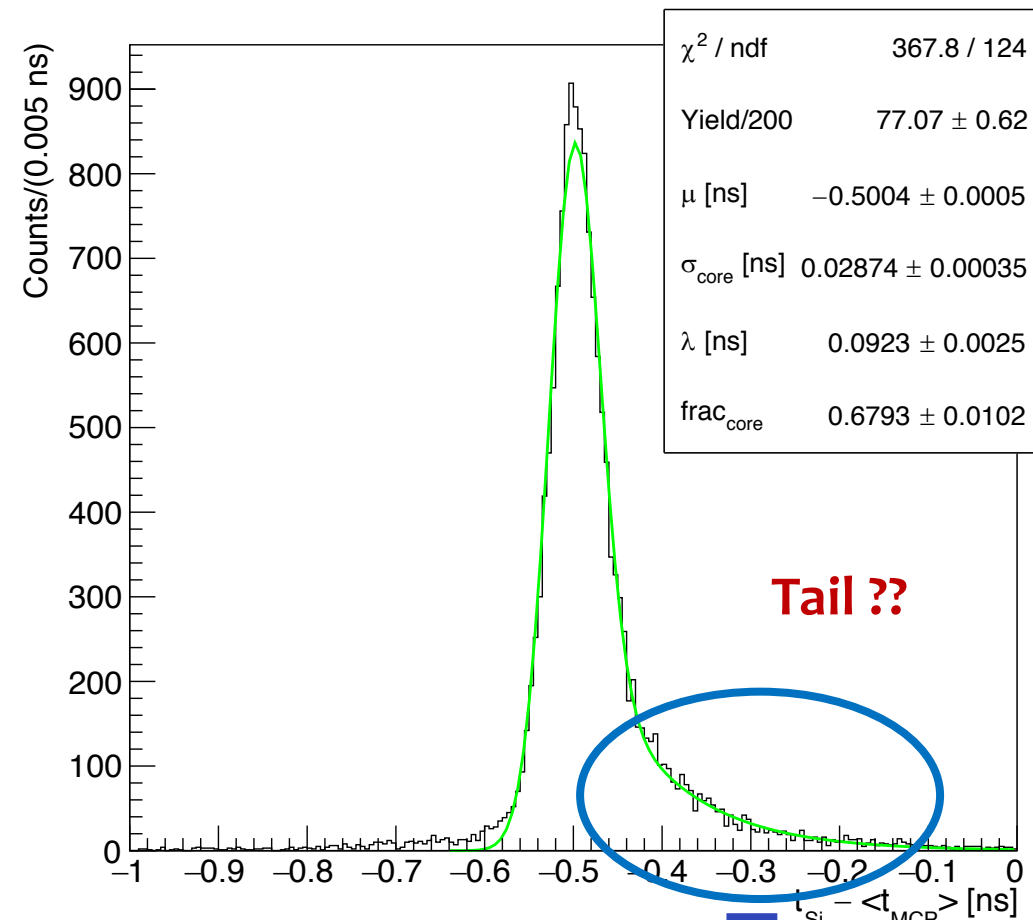


FIT: $f \cdot \text{Gaus}(\mu, \sigma) + (1 - f) \exp(\lambda) \otimes \text{Gaus}(\mu, \sigma)$

Test beam results: Time resolution (2)



Si-sensor time resolution after MCP time resolution subtraction for different V_{bias}



Combination of 3 main effects:

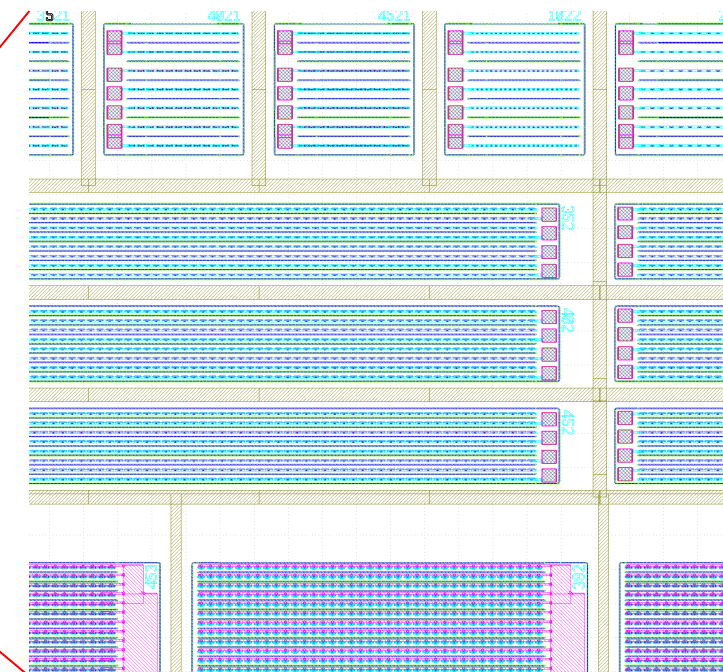
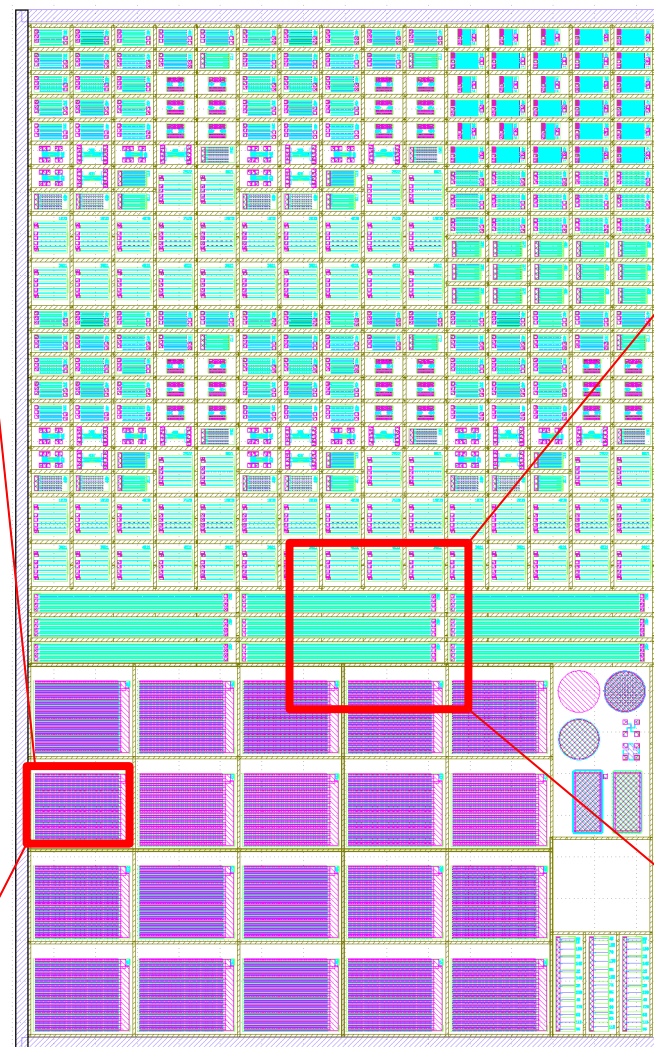
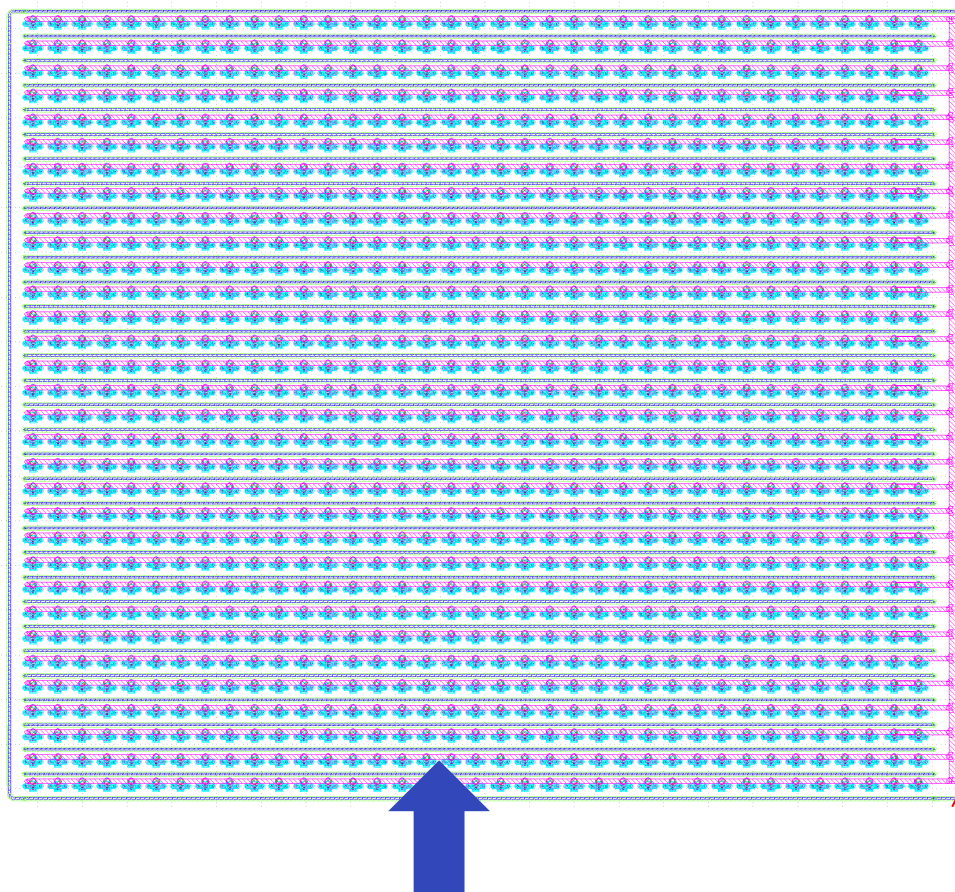
- Spurious signals (algorithm and in-time EMI noise)
- Boundary effects (neighbour un-read pixels)
- Weak field spots

Conclusions ...

- Unprecedented results on trench 3D Si pixels timing performance have been presented
- Results were obtained on wire-bonded sensors (x10 of nominal pixel capacitance)
- The time resolution of trench 3D sensor, $55 \times 55 \times 150 \mu\text{m}^3$, under laser beam has been measured being around **20 ps** under 1-MIP-estimated deposit charge.
- The time resolution of the same sensor measured under a $270 \text{ MeV/c } \pi^+$ beam has been measured $\approx$ **27 ps @ $V_{\text{bias}} = -140 \text{ V}$**
- **O(6%) Tails** require further studies. However they are naturally suppressed in a (multi-point) tracking system.
- **3D devices confirm their theoretical excellent performance in timing. Trench geometry shows up being the right direction to go**
- Up to now, **electronics** is the limiting factor to sensor and system performance
- TIMESPOT is developing **optimized electronics** necessary to possibly increase the obtainable target performance

... and very next Perspectives

- New batch of 3D-trench sensors has been launched



- Electronics: design of a 28-nm CMOS ASIC is at an advanced stage. A 32x32 pixels readout circuit will be submitted for production next summer.